

ABSTRACT OF THE DISCLOSURE

5 Comprising a first step of supporting a substrate
formed with a scintillator on at least three protrusions
of a target-support element disposed on a vapor deposition
table so as to keep a distance from said vapor deposition
table; a second step of introducing said vapor deposition
table having said substrate supported by said target-support
element into a vapor deposition chamber of a CVD apparatus;
10 and a third step of depositing an organic film by CVD method
onto all surfaces of said substrate, provided with said
scintillator, introduced into said vapor deposition
chamber.

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